

## INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

2002DE422

Application Number

10/518,315

Applicant(s)

Uwe FALK et al.

Filing Date

December 16, 2004

Group Art Unit

1794

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
		US 3,440,174	4/22/1969	Albrecht				
		US 6,277,476 B1	8/21/2001	Shaw-Klein et al.				
		US 6,358,495 B1	3/19/2002	Nishihama et al.				

## FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
	JP 2000-63721 A	2/29/2000	JAPAN				
	JP 2000-203835 A	7/25/2000	JAPAN			✓	
	JP 2000-344509 A	12/12/2000	JAPAN			✓	

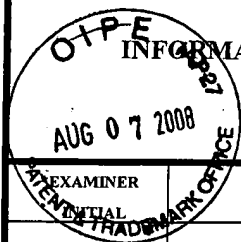
## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Copy of Office action dated June 26, 2008 in co-pending US serial No. 10/451,931. (NOTE: The document cited in the Office Action, US 3,440,174, is not enclosed as it is already of record in the above application.)
		Translation of JPO Office Action issued 2/14/2008 in Japanese Patent Application No. 2002-556121 corresponding to US Serial No. 10/451,931.

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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English Language Abstract of JP 2000-203835 A.

English Language Abstract of JP 2000-344509 A.

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